

## CERTIFICATE OF FACSIMILE TRANSMISSION

I hereby certify that this paper is being facsimile transmitted to the Patent and Trademark Office on the date shown below.

Deeba Anwar

name of person signing certification

  
SignatureFebruary 19, 2004  
Date**FAX TRANSMISSION COVER SHEET**RECEIVED  
CENTRAL FAX CENTER

FEB 19 2004

To: Examiner Kripa Sagar  
Group Art Unit 1756 ✓

Company Name: United States Patent and Trademark Office

Fax Number: (703) 872-9306

From: Warren M. Cheek, Jr.  
Wenderoth, Lind & Ponack

Date: February 19, 2004

In re application of: Kazuyuki NITTA et al.  
Serial No. 09/987,718  
Filed November 15, 2001

OFFICIAL

\*\*\*\*\*

TOTAL NUMBER OF PAGES TRANSMITTED, INCLUDING COVER SHEET 3

## CONFIDENTIALITY

The documents transmitted herewith contain confidential and/or privileged information intended only for the use of the person or entity to whom addressed. If you are not the intended recipient, or an agent of the recipient responsible for delivering it to the intended recipient, then you have received this transmission in error and are asked to promptly advise us by telephone or fax, and return the document to us by mail. Unauthorized copying, distribution, disclosure or other use of this information by anyone other than the intended recipient or their designee is prohibited.

\*\*\*\*\*

IF THERE ARE ANY PROBLEMS WITH THIS TRANSMISSION  
OR IF YOU HAVE NOT RECEIVED ALL OF THE PAGES  
PLEASE CALL (202) 721-8200.

Fax Operator: D. Anwar

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

RECEIVED  
CENTRAL FAX CENTER

FEB 19 2004

OFFICIAL

In re application of : Confirmation No. 7678  
Kazuyuki NITTA et al. : Docket No. 2001\_1703A  
Serial No. 09/987,718 : Group Art Unit 1756  
Filed November 15, 2001 : Examiner K. Sagar

METHOD FOR FORMING A HOLE-  
PATTERNED PHOTORESIST LAYER

---

**SUPPLEMENTAL RESPONSE**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This is further to Applicants' Response dated February 4, 2004.

Several minor clerical errors have been noted in the last complete paragraph on page 2 of the Response.

That paragraph in its entirety should read:

It is understood from 1:21 ~~and~~ to 2:20 of Bantu that the by-product of a low boiling point, which is a dissociated protective group by interaction of an acid, is vaporized by heating and may be deposited as a contaminant onto the lens. The resist film also causes shrinkage by the influence thereof. The object of Bantu's method in using a crosslinking agent is to solve these problems by crosslinking the resin with the crosslinking agent thus to increase the heat resistance of the resin and to decrease formation of the by-product of low boiling point (2:27-37) so that, as a result, the resist film becomes less susceptible to shrinkage.

Favorable action and allowance is kindly solicited.

Respectfully submitted,

Kazuyuki NITTA et al.

By: Warren M. Cheek, Jr.  
Warren M. Cheek, Jr.  
Registration No. 33,367  
*for*  
Matthew Jacob  
Registration No. 25,154  
Attorney for Applicants

WMC/da  
Washington, D.C. 20006-1021  
Telephone (202) 721-8200  
Facsimile (202) 721-8250  
February 19, 2004